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APPLICATION NO. FIRST NAMED INVENTOR ATTORNEY DOCKET NO. FILING DATE CONFIRMATION NO. 10/656,312 09/05/2003 Sylvia H. Pas TI-22398.1 8214 7590 04/28/2004 EXAMINER TEXAS INSTRUMENTS INCORPORATED AHMED, SHAMIM P O BOX 655474, M/S 3999 ART UNIT PAPER NUMBER DALLAS, TX 75265 1765

DATE MAILED: 04/28/2004

Please find below and/or attached an Office communication concerning this application or proceeding.

			m
,	Application No.	Applicant(s)	-
Office Action Summary	10/656,312	PAS, SYLVIA H.	
	Examiner	Art Unit	
	Shamim Ahmed	1765	
The MAILING DATE of this communication appeariod for Reply	opears on the cover sheet wit	h the correspondence address -	.=
A SHORTENED STATUTORY PERIOD FOR REPI THE MAILING DATE OF THIS COMMUNICATION - Extensions of time may be available under the provisions of 37 CFR 1 after SIX (6) MONTHS from the mailing date of this communication. - If the period for reply specified above is less than thirty (30) days, a reg. - If NO period for reply is specified above, the maximum statutory period - Failure to reply within the set or extended period for reply will, by statu Any reply received by the Office later than three months after the maili earned patent term adjustment. See 37 CFR 1.704(b).	136(a). In no event, however, may a re ply within the statutory minimum of thirty d will apply and will expire SIX (6) MONT tte, cause the application to become ABA	ply be timely filed (30) days will be considered timely. HS from the mailing date of this communications NDONED (35 U.S.C. § 133).	ation.
Status			
1)⊠ Responsive to communication(s) filed on <u>05</u> :	September 2003.		
	is action is non-final.		
3) Since this application is in condition for allow		ers, prosecution as to the merits	s is
closed in accordance with the practice under	•	·	
Disposition of Claims			
4) Claim(s) 14-20 is/are pending in the application	on.		
4a) Of the above claim(s) is/are withdra	awn from consideration.		
5) Claim(s) is/are allowed.			
6)⊠ Claim(s) 14-20 is/are rejected.		·	
7) Claim(s) is/are objected to.			
8) Claim(s) are subject to restriction and/	or election requirement.		
Application Papers			
9)☐ The specification is objected to by the Examin	ner.		
10)⊠ The drawing(s) filed on <u>05 September 2003</u> is	s/are: a)⊠ accepted or b)□	objected to by the Examiner.	
Applicant may not request that any objection to the	e drawing(s) be held in abeyand	ce. See 37 CFR 1.85(a).	
Replacement drawing sheet(s) including the corre	ction is required if the drawing(s	s) is objected to. See 37 CFR 1.12	.1(d).
11) The oath or declaration is objected to by the E	Examiner. Note the attached	Office Action or form PTO-152	<u>!</u> .
Priority under 35 U.S.C. § 119			
12) ☐ Acknowledgment is made of a claim for foreig a) ☐ All b) ☐ Some * c) ☐ None of:		119(a)-(d) or (f).	
1. Certified copies of the priority documer			
2. Certified copies of the priority documer			
3. Copies of the certified copies of the pri		eceived in this National Stage	
application from the International Bures	` ' ' '		
* See the attached detailed Office action for a lis	st of the certified copies not r	eceived.	
Attachment(s)			
1) Notice of References Cited (PTO-892)	4) Interview St	ummary (PTO-413)	
2) Notice of Draftsperson's Patent Drawing Review (PTO-948)	Paper No(s)	/Mail Date	
3) Information Disclosure Statement(s) (PTO-1449 or PTO/SB/08 Paper No(s)/Mail Date	5) Notice of Int	formal Patent Application (PTO-152)	

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DETAILED ACTION

Claim Objections

1. Claim 15 is objected to because of the following informalities: in claim 15, line 3, the use of "a" is unnecessary between the phrase "the " and "transfer chamber".

Appropriate correction is required.

Claim Rejections - 35 USC § 112

- 2. The following is a quotation of the second paragraph of 35 U.S.C. 112:
 - The specification shall conclude with one or more claims particularly pointing out and distinctly claiming the subject matter which the applicant regards as his invention.
- 3. Claims 14-20 are rejected under 35 U.S.C. 112, second paragraph, as being indefinite for failing to particularly point out and distinctly claim the subject matter which applicant regards as the invention.
- 4. Claim 14 recites the limitation "the oxide *layer*" in line 6. There is insufficient antecedent basis for this limitation in the claim.
- 5. Regarding claim 17, the phrase "solution comprises .049% to 49% HF" renders the claim(s) indefinite because it is unclear whether the percent (%) HF solution is by weight or by volume.

Claim Rejections - 35 USC § 102

6. The following is a quotation of the appropriate paragraphs of 35 U.S.C. 102 that form the basis for the rejections under this section made in this Office action:

A person shall be entitled to a patent unless -

(b) the invention was patented or described in a printed publication in this or a foreign country or in public use or on sale in this country, more than one year prior to the date of application for patent in the United States.

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7. Claims 14-19 are rejected under 35 U.S.C. 102(b) as being anticipated by Kikuchi (5,620,559).

Kikuchi discloses a process of removing oxide layer by exposing a semiconductor wafer comprises silicon substrate (104) in a HF processing chamber (105), wherein the HF is 10 % by volume (col.9, lines 32-62, figure 10).

Kikuchi also discloses that the silicon wafer is then align or line up for automatically transferring to a process module such as a deposition chamber (140) (col.11, lines 28-42 and figures 10 and 11).

8. Claims 14-16,18-20 are rejected under 35 U.S.C. 102(b) as being anticipated by Hawthorne et al (5,770,263).

Hawthorne et al disclose a process of removing oxide film from a silicon wafer surface including the process steps of exposing a silicon wafer to a vaporous solution of hydrofluoric acid (HF) for removing the oxide film, wherein the process is performed in a cluster tool is generally defined as a transfer module which transfer the wafer into a first chamber such as HF vapor clean and then the wafer is transfer to a second chamber such as a deposition chamber, in which at least one metallic film is intentionally deposited (col.4, lines 12-30).

As to claim 20, Hawthorne et al teach that the deposited film comprises polysilicon and tungsten (col.4, lines 12-13).

9. Claims 14-16,18-20 are rejected under 35 U.S.C. 102(b) as being anticipated by Huanga et al (5,670,431).

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Huanga et al disclose a process of deposition of a thin layer of silicon nitride on a semiconductor wafer substrate, wherein the substrate is subjected to a HF vapor cleaning process prior to the deposition process (col.5, lines 38-45).

Huanga et al also disclose that a wafer transfer system (52) transfer a single wafer from wafer loading station (58) to the HF cleaning system (56) and than to the film forming chamber (54) (col.6, line 65-col.7, line 15 and Figure 6).

Conclusion

10. The prior art made of record and not relied upon is considered pertinent to applicant's disclosure. Saga et al (5,679,171) disclose a cleaning process for oxide film using HF vapor.

Any inquiry concerning this communication or earlier communications from the examiner should be directed to Shamim Ahmed whose telephone number is (571) 272-1457. The examiner can normally be reached on M-Thu (7:00-5:30) Every Friday Off.

If attempts to reach the examiner by telephone are unsuccessful, the examiner's supervisor, Nadine G Norton can be reached on (571) 272-1465. The fax phone number for the organization where this application or proceeding is assigned is 703-872-9306.

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Information regarding the status of an application may be obtained from the Patent Application Information Retrieval (PAIR) system. Status information for published applications may be obtained from either Private PAIR or Public PAIR. Status information for unpublished applications is available through Private PAIR only. For more information about the PAIR system, see http://pair-direct.uspto.gov. Should you have questions on access to the Private PAIR system, contact the Electronic Business Center (EBC) at 866-217-9197 (toll-free).

Shamim Ahmed Examiner Art Unit 1765

SA April 22, 2004